

ANTI-REFLECTIVE SIDEWALL COATED ALTERNATING PHASE SHIFT MASK AND FABRICATION METHOD

ABSTRACT

A method for fabricating a phase shift mask is provided. A trenched phase shift mask having portions of a light-blocking layer thereon is formed. A layer of anti-reflective material is then formed on the trenched phase shift mask and the portions of the light-blocking layer. The anti-reflective material is then removed on horizontal surfaces of the trenched phase shift mask and of the portions of the light-blocking layer.

FIG 10